

## 8 MeV electron beam irradiation effects on Al/n-CdS thin film Schottky barrier diode

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**Abstract:** Electron irradiation on the Al/n-CdS Schottky barrier diode (SBD) was carried out by using 8 MeV electrons over a range of doses from 10 kGy to 75 kGy. Current-voltage ( $I-V$ ) and capacitance-voltage ( $C-V$ ) characteristics of the SBD were studied at room temperature. Diode parameters such as the ideality factor, series resistance, and Schottky barrier height were calculated from forward  $I-V$  characteristics. Effects of irradiation on the carrier concentration, depletion layer width and barrier height were studied from  $C-V$  characteristic. The ideality factor, series resistance, reverse saturation current and depletion layer width were found to increase with the increase of radiation dose. The carrier concentration and barrier height were found to decrease with increase in electron irradiation dose.

**Keywords:** CdS thin film, current – voltage, capacitance – voltage characteristics, electron irradiation, Schottky barrier diode.

### I. Introduction

Cadmium sulphide (CdS) is an important semiconductor material for applications in electronic and optoelectronic devices such as solar cells [1, 2], non-linear integrated optical devices [2], photo detectors [2 - 4], optical waveguides [2], thin film transistors [5] etc. CdS generally shows n-type conductivity due to native donors resulting from sulphur vacancies. A wide variety of techniques such as evaporation [6], sputtering [7], chemical bath deposition (CBD) [5], spray pyrolysis [8], electrode position [9], close spaced sublimation [10], successive ionic layer adsorption reaction (SILAR) [11], spin coating [12], etc. have been employed for the deposition of CdS thin films.

The metal-semiconductor (MS) rectifying contacts, the Schottky barrier contacts, are widely used in photo detectors,  $\gamma$ -ray detectors, solar cells, microelectronics and integrated circuits [13]. A proper understanding of the properties of a given Schottky barrier contact is very important for its intended applications. The barrier height of a SBD depend on the factors such as work function of the metal and electron affinity of the semiconductor, doping concentration of the semiconductor, the existence of native interfacial insulator layer and its thickness, and density of interface defects states [14, 15]. Any mechanism that affects the Schottky barrier interface will lead to changes in the SBD performance [16]. In space applications, SBDs are continuously exposed to various particles such as electrons, neutrons, protons and alpha particles having energy ranging from a few keV to hundreds of MeV. That will induce lattice defects that can alter the electronic structure of the MS interface [13]. Thus, it is essential to study the effect of radiation on a given semiconductor SBD so as to find its suitability for space applications.

There are several reports on metal/CdS SBDs using metals such as Al, Au, Ag, and Te [17, 18]. Tascioglu et al. [17] studied the effect of metal work function on the barrier height of the metal/CdS/SnO<sub>2</sub>/In-Ga structures with several metals such as Ag, Au, Al, and Te. Several studies were reported on the Al/CdS SBDs [17, 18, 19] but the studies on radiation induced damages on the Al/CdS SBDs are scarce to the best of our knowledge. In the present work, the effect of 8 MeV electron irradiation on Al/n-CdS SBD prepared using spray pyrolysis deposited CdS thin film has been studied using  $I-V$  and  $C-V$  measurements.

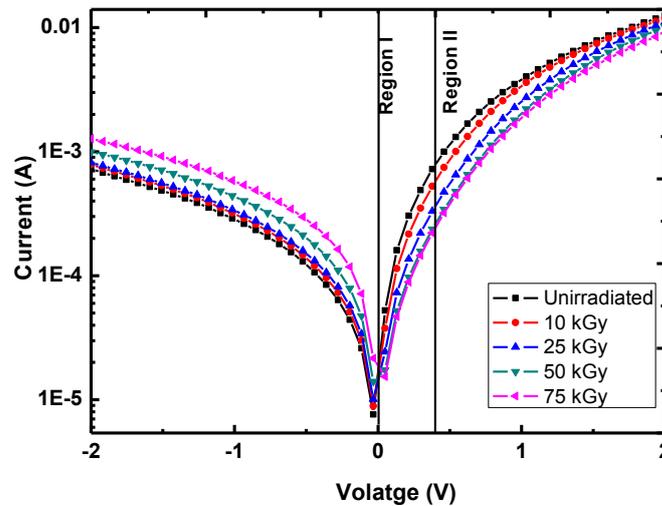
### II. Experimental Details

A simple and inexpensive spray pyrolysis method was used to deposit the CdS thin film. Aqueous solutions of 0.15M CdCl<sub>2</sub> and 0.15M (NH<sub>2</sub>)<sub>2</sub>CS were mixed in an appropriate quantities in order to get the precursor solution with [Cd]/[S] = 0.5. The solution mixture was then stirred well and sprayed on to the ITO coated glass substrates kept at 400 °C in an ambient atmosphere at a spray rate of 10 ml/min. The grown film was annealed for 15 minutes at 400 °C and allowed to cool naturally to room temperature. The Al/CdS SBD was prepared by depositing Al metal dot of 125 nm in thickness and 0.014 cm<sup>2</sup> area through a mask on the CdS film at a pressure of 2x10<sup>-5</sup> mbar using a HINDHIVAC vacuum coating unit - Model 12A 4. Ohmic contact was made by depositing indium on ITO. The prepared Al/CdS SBD was exposed to 8 MeV electron beam radiation over a range of doses from 10 kGy - 75 kGy using Microtron accelerator at Mangalore University. The salient features of the Microtron accelerator are detailed elsewhere [20].

*I-V* characteristics of the SBD were measured at room temperature, both before and after irradiation, using computer interfaced Keithley 236 source/measure unit at Microtron centre, Mangalore University. The *C-V* measurement was carried out before and after irradiation on the SBD at 1 MHz frequency using Agilent 4294 A LCR meter at CENSE, IISc, Bangalore.

### III. Results And Discussions

Fig. 1 shows the *I-V* characteristics of the Al/n-CdS SBD irradiated with 8 MeV electrons of various doses ranging 10 kGy-75 kGy. As shown in Fig. 1, the forward current decreased and the reverse current increased with increase in the irradiation dose. The forward  $\ln(I)$  versus *V* plot shows nearly a linear increase with increase in bias voltage up to ~0.4 V and this linear region is labelled as Region I in Fig.1. Above 0.4 V, the forward current-voltage characteristics show a non-linear behaviour. This nonlinear region of the forward *I-V* curve is labelled as Region II in Fig. 1.



**Fig. 1** *I-V* characteristics of Al/n-CdS SBD irradiated with various electron doses.

In moderately doped semiconductor SBDs the current flow can be described by thermionic emission theory [21]. Based on thermionic emission theory, *I-V* plot of the Al/n-CdS SBD in region I can be described by the equation [21]

$$I = I_s \left[ \exp\left(\frac{qV}{nkT}\right) - 1 \right] \tag{1}$$

with saturation current  $I_s$  is given by the equation

$$I_s = AA^{**}T^2 \exp\left(-\frac{q\phi_b}{kT}\right) \tag{2}$$

where  $q$  is the electron charge,  $k$  is the Boltzmann constant,  $V$  is the applied voltage,  $n$  is the ideality factor,  $A$  is the area of the diode,  $A^{**}$  is the Richardson constant, and  $\phi_b$  is the Schottky barrier height. Equation (1) can also be expressed as

$$\ln(I) = \frac{qV}{nkT} + \ln(I_s) \tag{3}$$

Therefore, the saturation current and the ideality factor can be obtained from the intercept and slope of the forward  $\ln(I)$  versus *V* plot using the equation (3). The measured ideality factor for the Al/n-CdS SBD was found to increase with the increase in the radiation dose as shown in the Table 1. The observed increase of ideality factor with the increase of the radiation dose may be due to the increase in the density of interface states [22].

From the saturation current, Schottky barrier height ( $\phi_b$ ) was calculated using the equation (2) as

$$\phi_b = \frac{kT}{q} \ln \left( \frac{AA^{**}T^2}{I_s} \right) \quad (4)$$

For calculating  $\phi_b$  for the Al/n-CdS SBD using equation (4),  $A^{**}$  was taken to be equal to  $12 \text{ AK}^{-2}\text{cm}^{-2}$  for n-CdS [19]. The obtained values of  $\phi_b$  decreased with the increase of radiation dose as shown in the Table 1. The decrease of  $\phi_b$  with the radiation dose was also observed by A Rao et al. [22] and S Krishnan et al. [23] for Au/n-Si and Al/p-Si SBDs, respectively. The decrease of  $\phi_b$  with increase in radiation dose may be due to the increase resistivity (decreasing concentration due to compensation) of CdS thin film.

For a Schottky with series resistance  $R_s$ , the I-V equation (1) becomes

$$I = I_s \left[ \exp \left( \frac{q(V - IR_s)}{nkT} \right) - 1 \right] \quad (5)$$

Equation (5) can be written as

$$\frac{dV}{d(\ln I)} = IR_s + \frac{nkT}{q} \quad (6)$$

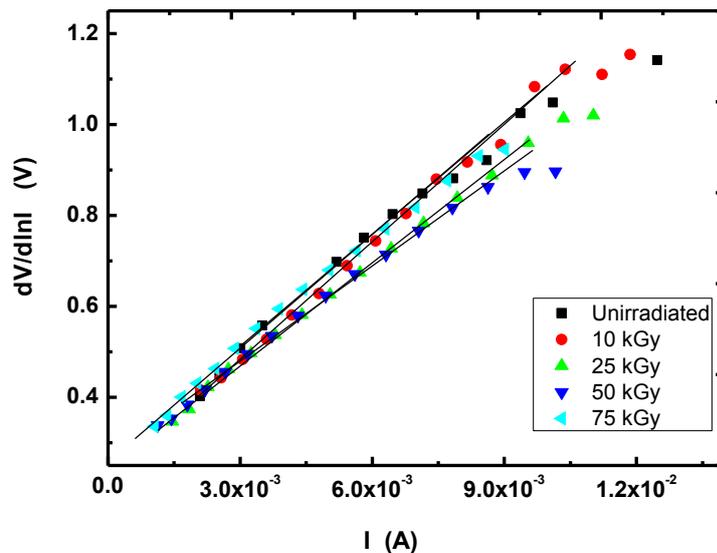


Fig. 2  $dV/d\ln I$  vs.  $I$  plot of Al/n-CdS SBD irradiated for various electron doses.

For Region II of the I-V plot, the series resistance and the ideality factor were obtained from the slope and intercept of  $dV/d\ln I$  versus  $I$  plot using equation (6). The  $dV/d\ln I$  versus  $I$  plot is shown in Fig. 2. The calculated values of series resistance  $R_s$  and ideality factor  $n$  are listed in the Table 1, the series resistance increased with the increase in the radiation dose. This may be due to the reduction in the product of mobility and free carrier concentration with radiation dose. Mobility may reduce with the increase in the radiation dose because of the radiation induced defect centres which act as scattering centres for charge carriers. Increase of defect centres also lead to the reduction in free carrier concentration [22, 24], thus decreasing the product of free carrier concentration and the mobility. Increase of series resistance may be the main cause for the decrease of the forward current with the increase of the radiation dose.

**Table 1.** Ideality factor ( $n$ ), series resistance ( $R_s$ ) and barrier height ( $\phi_b$ ) variation of Al/CdS SBD with radiation dose.

Dose (kGy)	Ideality factor		Series resistance ( $\Omega$ ) 0.4 V < V < 2 V	Barrier height (eV)
	0 < V < 0.4 V	0.4 V < V < 2 V		
Unirradiated	6.64	3.03	74.63	0.473
10	6.71	3.15	77.89	0.467
25	6.77	3.38	80.66	0.456
50	6.88	3.46	81.49	0.447
75	6.99	3.53	83.58	0.441

C-V characteristic is another important tool to study the electrical properties of a SBD. From the C-V measurements, the SBD diode parameters such as carrier concentration, built-in potential and depletion layer width ( $W$ ) can be found out. Hence, in order to find the irradiation induced changes in the properties of the Al/n-CdS SBD, C-V measurement was carried out both before and after exposing the diode to 8 MeV electron beam irradiation of 75 kGy. The room temperature C-V profiles of the unirradiated and electron beam irradiated Al/n-CdS SBD are shown in the Fig. 3. The C-V relation for an n-type semiconductor SBD is given by the equation [25]

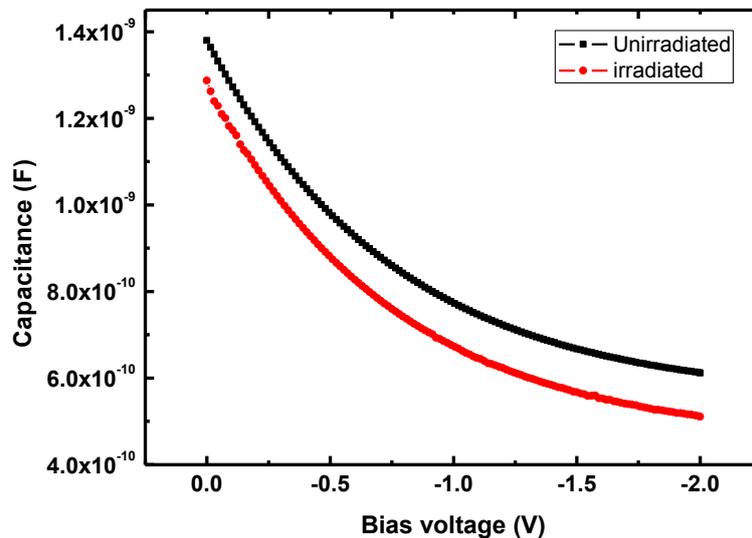
$$C = \frac{\epsilon_s \epsilon_0 A}{W} = A \left[ \frac{q \epsilon_s \epsilon_0 N_d}{2(V_{bi} + V)} \right]^{1/2}$$

(7)

where  $C$  is the capacitance,  $N_d$  is the carrier concentration,  $\epsilon_s$  is the dielectric constant of the semiconductor,  $\epsilon_0$  is the absolute permittivity and  $V_{bi}$  is the built in potential and  $V$  is the bias voltage. The dielectric constant for n-CdS was taken to be equal to 5.7 [26]. The depletion layer width of the Al/n-CdS SBD was calculated using the equation (7). The depletion layer width for the unirradiated Al/n-CdS SBD was found to be 4.59 nm at zero bias and 10.4 nm at -2 V bias. After 75 kGy electron irradiation the depletion layer width of the Al/n-CdS SBD was found to be 4.95 nm at zero bias and 12.4 nm at -2 V bias which shows electron irradiation induced increase in the depletion layer width.

Equation (7) can be rewritten as

$$\frac{1}{C^2} = \frac{2}{A} \frac{1}{q \epsilon_0 \epsilon_s N_d} [V_{bi} + V] \tag{8}$$



**Fig. 3** C – V characteristics of unirradiated and irradiated Al/CdS SBD.

Therefore, as per equation (8), the value of the carrier concentration  $N_d$  and the built-in potential  $V_{bi}$  of the Al/n-CdS SBD can be found from the slope and intercept of  $1/C^2$  versus  $V$  plot, respectively. Fig. 4 shows the dependence of  $1/C^2$  on applied voltage for the unirradiated and the electron irradiated Al/n-CdS SBD. The  $1/C^2$  versus  $V$  plot is linear only for low bias voltages, and as the bias voltage increases, it deviates from linearity. This may be due to a high leakage current in this SBD as shown in the I-V Characteristics in Section

3.1. The carrier concentration obtained from the C-V measurement was found to be  $1.84 \times 10^{23} \text{ m}^{-3}$  and  $1.46 \times 10^{23} \text{ m}^{-3}$  before and after irradiation, respectively. The built in potential obtained from the C-V measurement was found to be 0.121 eV and 0.132 eV before and after irradiation, respectively. The slight decrease in the carrier concentration after irradiation may be due to the irradiation induced electron capture levels or acceptor like defects at the Al/n-CdS junction [24].

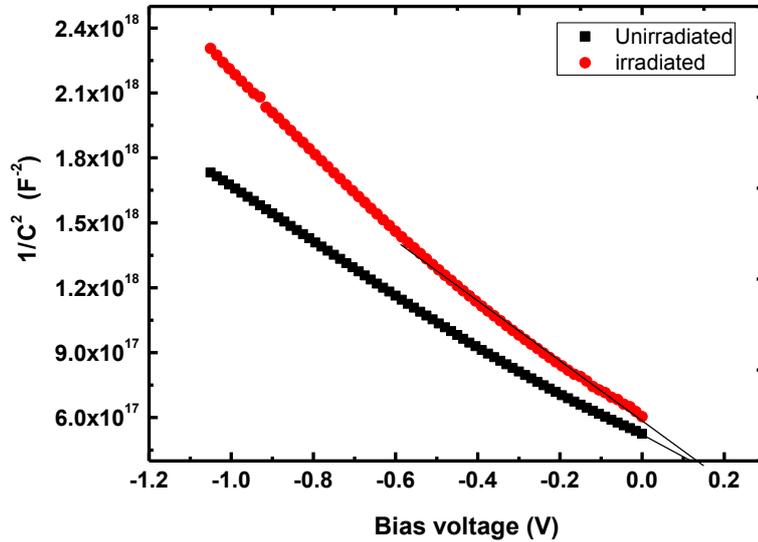


Fig. 4  $1/C^2$  vs  $V$  plot of pristine and irradiated Al/CdS SBD.

The potential difference between the Fermi level and the top of the valence band ( $V_p$ ) in CdS was calculated using equation [18],

$$V_p = kT \ln \left( \frac{N_C}{N_d} \right) \quad (9)$$

where  $N_C$  is the density of states in the conduction band of CdS, equal to  $2 \times 10^{24} \text{ m}^{-3}$  [27].  $V_p$  was found to be 0.0068 eV and 0.0062 eV before and after irradiation, respectively.

The effective barrier height ( $\phi_b$ ) was calculated from C-V measurements using equation,

$$\phi_b = V_{bi} + V_p \quad (10)$$

The effective barrier height ( $\phi_b$ ) was increased from the unirradiated value of 0.127 eV to 0.138 eV after irradiation. The value of barrier height obtained from C-V measurement was smaller than that obtained from I-V characteristics. This may be due to the presence of an interface layer or due to spatial inhomogeneities at the MS interface of abrupt Schottky contact [24].

#### IV. Conclusion

CdS thin film was deposited on ITO coated glass substrate by spray pyrolysis. Al/n-CdS SBD was formed by depositing Al metal contact on n-CdS film by thermal evaporation. Irradiation induced changes in the Al/n-CdS SBD parameters were studied from I-V and C-V measurements both before and after irradiation. Increase in the ideality factor and the series resistance with irradiation were observed. A decrease in the Schottky barrier height and the increase in reverse current were also observed for irradiated sample. The degradation of SBD properties after irradiation may be due to irradiation induced defect states at the Al/n-CdS junction. Also, Carrier concentration decreased from the unirradiated value of  $1.84 \times 10^{23} \text{ m}^{-3}$  to  $1.46 \times 10^{23} \text{ m}^{-3}$  after irradiation.

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